SENTECH Erfolg durch Leistung

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SE 850 Z DUV
UV-VIS-NIR SENresearch
Spectroscopic Ellipsometer

Spectral range: 190nm ... 1700nm

Product description

- Fast and precise ellipsometric analysis in a broad spectral range of 190 nm to 1700 nm
- STEP SCAN measuring mode combined with diode arrays for the UV-VIS and NIR, compensator and polarizer tracking for most accurate and complete sample analysis
- **SpectraRay/3** – comprehensive software for spectroscopic ellipsometry including sophisticated multiple angle, multiple-sample, and combined photometric data analysis, programmable customer interface and advanced reporting
- Easy operation for both, experts and beginners
- SENTECH material library and sample applications for efficient modeling

1   General description

The UV / VIS / NIR spectroscopic ellipsometer **SE 850 Z DUV** measures thickness and optical parameters of bulk materials, single and multiple layers, interfaces, thin and thick films.

The **SE 850 Z DUV** is tailored for high demanding applications like the measurement of thin transparent films on glass, light emitting and semiconducting polymers, multiple layer stacks of semiconducting materials, low-e stacks on window pane and advanced microelectronic applications like SOI, high-k and low-k materials. Anisotropic and non-uniform samples can be analyzed.

The **SE 850 Z DUV** is a high performance spectroscopic ellipsometer, based on fast diode array detection in the UV / VIS spectral range and fast interferometer modulated detection in the NIR spectral range. The **SE 850 Z DUV** is characterized by both fast data acquisition and full spectral resolution.

The **SE 850 Z DUV** is based on the Step Scan Analyzer operation principle. The reflected light is simultaneously analyzed at fixed analyzer positions using an optical multichannel analyzer in the UV / VIS and a broadband detector in the NIR. The Step Scan Analyzer measurement mode ensures an outstanding S / N ratio even for low light level applications. The UV / VIS spectrophotometer consists of a grating and a CCD array. A photodiode array is used as detector in the NIR.

The **SE 850 Z DUV** incorporates automatic fiber switches for the seamless transition between UV / VIS and NIR spectral range. The setup allows the reflected light to be switched between UV / VIS detection channel and NIR detection channel.

The ellipsometer setup contains Polarizer – Compensator – Sample – Analyzer (PCSA) assuring the measurement of the degree of polarization and to compensate for depolarization effects caused by non-uniform samples, rough surfaces, limited spectral resolution and focusing angle. Using a compensator the ellipsometric angle Δ can be measured in the whole range from 0 - 360 degrees with extreme accuracy and ultimate precision. Additionally the compensator is highly stabilized against changes of the environmental temperature to provide lowest drift and lowest measurement error even at Delta = 0 deg.

The **SE 850 Z DUV** data acquisition can be tuned for highest measurement accuracy for each individual application. The polarizer position is computer controlled and can be set to dedicated values according to the optical response of the sample (polarizer tracking).

Precise sample alignment is vital for highly accurate ellipsometric measurements. The **SE 850 Z DUV** features the Auto Collimating Telescope (ACT) for the tilt and an optical microscope for the focus of the sample.

Smooth operation of the instrument is guaranteed by SENTECH's controller concept. While the software runs on a state of the art PC under Windows 7 the complete hardware is separately controlled by its own embedded microcontroller.

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SENTECH's proprietary ellipsometer software **SpectraRay/3** comprises two modes of operation: recipe mode and interactive mode. The recipe mode allows for easy execution of repetitive applications. In interactive mode, ellipsometric measurements are enhanced by an interactive, guiding graphical user interface. The operation of **SpectraRay/3** is very intuitive and satisfies the demands for ease of use and multiple user operation.

SpectraRay/3 includes data acquisition, modeling, fitting, and extended reporting of ellipsometric, reflection, and transmission data. It supports variable angle, multi-experiment, and combined photometric measurements. **SpectraRay/3** contains a huge library of materials data based on SENTECH measurements and literature data as well. The large number of dispersion models allows modeling of nearly any type of material.
The scripting capability makes it very flexible to automate routine measurements, to tailor it for dedicated applications and to control third party hardware like sensors, heaters or a cryostat.

The **SE 850 Z DUV** comprises the mechanical setup with a manual goniometer for multiple angle measurements, the optical components, the optical fibers, an electronic rack containing the UV/VIS spectrophotometer, the UV/VIS light source, the ellipsometer controller with electronic boards and microcontroller unit, FTIR spectrometer, desktop PC with Windows 7 and SENTECH **SpectraRay/3** software

2   Technical Specifications

General:

Spectral Range:	190 nm – 1700 nm
Max. sample size	6", optional 8" and 300 mm
	Maximum substrate thickness 7 mm
	Larger and/or thicker samples on request
Layers	Opaque or transparent
	Software allows for an unlimited number of layers to be analyzed
	The practical number of layers that can be measured depends on the sample. More than five layers is possible for almost all samples

Optical and mechanical Components:

Ellipsometer operation principle:	**PCSA setup:**
	P: polarizer

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C: compensator (super-achromatic)

S: sample

A: Step Scan Analyzer

Light source:	UV / VIS / NIR: Deuterium Tungsten- Halogen combined lamp NIR: optional 20 W Tungsten-halogen lamp
Polarizer / Analyzer:	Broadband MgF2 Rochon prisms Computer controlled analyzer and polarizer Extinction rate: 10^{-5} Angular precision: better than 0.01°
Compensator	Compensators for UV-VIS and NIR spectral range The use of compensator enables the user to measure the ellipsometric angle Δ in the whole data range from 0° to 360° with extreme accuracy.
Measurement spot:	Manually variable beam diameter from 1 mm to 4 mm Optional: 200 μm micro spot, smaller spot size on request
Spectral discrimination:	For the UV / VIS region the detection is based on the Step Scan Analyzer measurement mode and fast CCD array detection: The reflected light is analyzed at fixed analyzer positions with an optical multichannel analyzer, consisting of a grating and a CCD array detector. Spectral resolution UV-VIS: 4 nm FWHM at 150 µm slit width Spectral resolution NIR: 6 nm FWHM Ellipsometric spectra are measured automatically in the whole spectral range of both detection systems.
Detector:	UV / VIS: highly sensitive Si CCD array detector, NIR: InGaAs diode array

Sample stage:	Fixed sample stage with 150 mm sample platform, height- and tilt adjustable
	Optional: mapping stages 50 mm x 50 mm (manual and motorized), 150 mm x 150 mm (motorized), 200 mm x 200 mm (motorized), 300 mm (r, theta)-stage (motorized), Other stages on request
	Vacuum chuck.
Sample holder for T measurements	Fast exchange with standard sample stage via quick lock
	90deg measurement position of ellipsometer arms, sample is clamped to holder
	Minimal sample size 10 mm
	Other configurations on request
Goniometer:	Mechanical Goniometer, 40° - 90°, set in 5° steps Precision: better than 0.02 °
	Optional:
	Computer controlled goniometer, incident angle range from 40°-90°, minimum step width 0.002°, precision: better than 0.01°
	Extended angle range from 20° to 90°
Sample adjustment::	Auto Collimating Telescope (ACT) and optical microscope for precise sample alignment (height and tilt)
	Optional: • Video camera option for ACT, it also gives a picture of the measurement area on the PC monitor
Measuring Time:	UV - VIS: Typical 10 s
	NIR: ~20 s
Controller:	Modular unit with bench top ellipsometer optics and goniometer.
	Separate rack contains electronic boards, microcontroller unit, power supplies, light sources, spectrophotometer

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Computer:	State of the art HP desktop PC, TFT-monitor, keyboard, mouse, Windows 7 Professional operation software

| Output device: | Software interface to export and import spectroscopic data. Network card |
| | Inkjet printer compatible |

| Power requirements: | Rated voltage: 115/230 VAC auto select (100-132 VAC or 207-264 VAC), Rated frequency: 50-60 Hz, Rated power: 550 W, |
| | Other common line voltages available |

| Environment: | Cleanroom (Class 100) compatible |

3 Data acquisition and analysis software: SpectraRay/3

Features:	**SpectraRay/3** operating and analysis software comprises

- Interactive and recipe mode of operation
- Automated system Calibration
- Automatic setting up of optical and mechanical components
- Easy and guided software operation including data acquisition, modeling, fitting and reporting
- Complete experiments can be saved as recipes
- Recipe mode for routine applications
- Mapping module for computer controlled samples stages (description see also mapping options)
- Advanced reporting of measured and fitted spectra, measurement data, user comments, sample information in a Word-like environment

Measurement output:	• Ellipsometric angles ψ; Δ, Fourier coefficients s_1, s_2 vs. energy, wavelength or wavenumber (related to sample position, angle of incidence) of single or multiple angle or time dependent measurements

- Mueller matrix elements
- Polarized reflectivity R_p, R_s and transmission
- Dispersion relation
- Dielectric function
- Degree of polarization
- Graphic representations of measured and calculated ellipsometric

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spectra
- Data clipping to selected wavelengths and angles without changing original data
- Merge function for combining sets of different wavelength ranges
- Combine function for combining sets of different data in one file
- Reduction of data as modulo or average
- Extract angle traces from multiple angle and time dependent data

Modelling, simulation and fit:	**SpectraRay/3** is able to fit any multilayer structure (single film, layer stack, periodical groups of stacks) for ψ, Δ; tan ψ, cos Δ and Fourier coefficients, transmission, reflection etc. This includes anisotropic substrates and layers (separate software license).

- Large material library (more than 200 data sets), user expandable and application adaptable

- Large set of dispersion relations to describe the optical properties of layers and bulk materials: data file (data table), 2D table, Cauchy, Sellmeier, Schott, Drude-Lorentz, Lorentz, Urbach, Leng, Tauc-Lorentz, Cody-Lorentz, Brendel, Hamberg, Sernelius, Forouhi-Bloomer, Afromovitz, Tanguy, spectral combination layer for combining different dielectric models, user defined dispersion formula, dispersion formula for uniaxial and biaxial anisotropic materials, dispersion formula for periodic layer stacks

- Each layer of a model stack can be a homogeneous film, an interface, a surface roughness, a homogeneous growing layer, an index gradient (effective medium approximations: Maxwell-Garnett, Bruggemann, Lorentz-Lorenz, Clausius-Mossotti)

- Material gradients can be modeled by one of the following type of functions: linear, exponential, error function like, Gaussian (symmetrical or asymmetrical) like, parabola like.

- Fast regression algorithms for fitting calculated spectra to measured spectra

- Graphical representation of fitted spectra

Fit of composite data:	The fit algorithm does not only allow fitting of ellipsometric data but also transmission and reflection spectra as well. The fit can be based on multiple measurements (Ψ, Δ, R, T) and different samples with same layer material. External data of other instruments can be imported as ASCII data and analysed / fitted
Fit parameters:	Customer defined, depending on the model. There is no fundamental limit for the number of fit parameters or layers in a layer stack. Fit parameters could be e.g.: film thickness, refractive index, extinction coefficient, constituent fractions, incident angle, composition profile, temperature, and time.

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Fit statistics:	Fit error and correlation matrix are calculated. Device -, wavelength - and sample alignment errors can be taken into account.
File management functions:	The software is based on Windows 7 and provides full file management functions.
User management:	The software provides full user level management and allows user specific assignment of rights on a function level basis.
Recipe module:	Push button operation of routine applications (recipes), A recipe includes the hardware settings, measurement conditions, model and measured data. A set of standard recipes is delivered with the software. New recipes can be built up by adapting already existing recipes or importing corresponding data from the interactive operation part of **SpectraRay/3** after a new ellipsometric application was solved. A measurement can be directly started after loading a new recipe. All settings can be optimized / set by the user (password based user management available). The measured results (measured and fitted spectra, fit parameters) are shown in the operation window of the module. Recipes can be used in mapping applications as well if computer controlled mapping is available
Customized user interface:	**SpectraRay/3** includes a software package to develop user defined measuring and operation routines based on an easy to use script language.

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4 Optional items

SE 802	Computer controlled goniometer, precision 0.01°
SE 800-3	Micro spot option, 200 µm spot diameter in the UV/VIS, 100 µm spot on request
SE 61	Video camera for alignment in lieu of eyepiece, frame grabber, microscopic image
SE PXY	Manual x-y stage with 50 mm travel
SE PSV	Vacuum chuck in lieu of standard sample stage
SE PSD	Rotational element with quick lock in lieu of standard sample stage
SE 800-PST	Sample holder with quick lock for transmission measurements
SE 14	Mapping stage, x = 50 mm, y = 50 mm sample stage (including vacuum chuck), 150 mm sample platform extensive mapping software to define scan raster and to display scans in various ways
SE 15	Mapping stage, x = 150 mm, y = 150 mm sample stage (including vacuum chuck), 150 mm sample platform extensive mapping software to define scan raster and to display scans in various ways
SE 16	Mapping stage, x = 200 mm, y = 200 mm sample stage (including vacuum chuck), 200 mm sample platform extensive mapping software to define scan raster and to display scans in various ways
SE 17	Mapping stage, r,ϑ-stage for 300 mm wafers, 150 mm travel length (including vacuum chuck), 300 mm sample platform extensive mapping software to define scan raster and to display scans in various ways
SE AF	Autofocus option in combination with SE 800 mapping option
SE AFT	Auto height and tilt adjustment
SE 800-30	Reflectometer based on FTPadv, spectral range 450-920 nm, 80 µm spot size
SE 20	Liquid cell for in situ measurements, Teflon, one pair of windows liquid at rest
SE CFH26	Liquid cell 26 ml volume heated up to 70°C, incidence angles 50°, 60°, 70°, fluid flow, Cells with other parameters on request
SE K20	SENTECH thin film test wafer, nominal 20 nm SiO2 on Si
SE K100	SENTECH thin film test wafer, nominal 100 nm SiO2 on Si
SE K400	SENTECH thin film test wafer, nominal 400 nm SiO2 on Si
SE 51	Second SpectraRay license for work station
SE 5A	SpectraRay/3 license for anisotropic sample analysis
SE 800-2C16M	Extension to SE 850 Z DUV for the measurement of 16 Mueller matrix elements